



Fig. 3

RECEIVE RAW SPECTRAL DATA
REPRESENTATIVE OF THE CONTENT OF A
PLURALITY OF VOLATILES DESORBED
FROM A WAFER

420

PROCESS THE RAW SPECTRAL DATA
TO DETERMINE THE PRESENCE OF A
RESIDUAL MATERIAL ON THE
WAFER

430

CONTROL A PROCESS FLOW OPERATION TO REDUCE THE AMOUNT OF THE RESIDUAL MATERIAL ON THE WAFER RESPONSIVE TO THE RESULTS OF PROCESSING THE RAW SPECTRAL DATA

Fig. 4

